	Application No.	Applicant(s)	_
	10/767,559	LIST ET AL.	
Notice of Allowability	Examiner	Art Unit	_
	Nguyen T Ha	2831	
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication IGHTS. This application is subject to	plication. If not included will be mailed in due course. THIS	e
1. This communication is responsive to <u>01/28/2004</u> .			
2. The allowed claim(s) is/are <u>1-26</u> .			
3. $\boxtimes$ The drawings filed on <u>28 January 2004</u> are accepted by th	e Examiner.		
<ul> <li>4. Acknowledgment is made of a claim for foreign priority unally All b) Some* c) None of the: <ol> <li>Certified copies of the priority documents have</li> <li>Certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received:</li> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.</li> </ul>	e been received. e been received in Application No cuments have been received in this of this communication to file a reply	national stage application from the	
5. A SUBSTITUTE OATH OR DECLARATION must be subminformal PATENT APPLICATION (PTO-152) which give 6. CORRECTED DRAWINGS (as "replacement sheets") must	es reason(s) why the oath or declara	'S AMENDMENT or NOTICE OF tion is deficient.	
(a) ☐ including changes required by the Notice of Draftspers		948) attached	
1)  hereto or 2) to Paper No./Mail Date	- ·	5 10, 411451154	
(b) including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the C	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT			
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☑ Notice of Draftperson's Patent Drawing Review (PTO-948)		atent Application (PTO-152)	
,	Paper No./Mail Dat	te	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date <u>0104 &amp; 0604</u></li> </ol>	08), 7. 🛭 Examiner's Amendr	ment/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. Examiner's Stateme 9. Other  ANTHONY DINKINS PRIMARY SYAMORE	ent of Reasons for Allowance	
U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04)	otice of Allowability	Part of Paper No./Mail Date	
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## **DETAILED ACTION**

## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Claim 18, line 1, please change "a" to - - an - -.

# Allowable Subject Matter

2. Claims 1-26 are allowed.

The following is an examiner's statement of reasons for allowance:

With respect to claims 1-6, the prior art alone or in combination does not teach the limitation of an apparatus comprising: a planarized metal interconnect line coupled to a bottom electrode of an electrically decoupling capacitor wherein a top electrode of the electrically decoupling capacitor is coupled to a flip chip bump contact such that the capacitor being disposed between and aligned between at least a portion of the metal interconnect line and the bump contact.

With respect to claims 7-12, the prior art alone or in combination does not teach the limitation of an apparatus comprising: a bump contact coupled to a decoupling capacitor and second top metal voltage bias line such that the capacitor is disposed between and aligned between at least a portion of the first top metal voltage bias line

and the bump contact, the second top metal voltage bias line having a different purpose than the first top metal voltage bias line coupled to the capacitor.

With respect to claims 18-21, the prior art alone or in combination does not teach the limitation of an apparatus comprising: a bump contact contacting a top electrode material such that the top electrode material being disposed between and aligned between at least a portion of the layer of metal and the bump contact.

With respect to claims 22-26, the prior art alone or in combination does not teach the limitation of an apparatus comprising: a bump contact contacting a capacitor stack through a removed portion of a passivation layer over a top of the capacitor stack such that the capacitor stack being disposed between and aligned between at least a portion of the layer of metal and the bump contact, the bump contact also contacting a second metal power bias voltage line.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### Citation Relevant of Prior Art

- 3. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- Chen et al. (US 6,812,088) disclose a method for making a new metal a. insulator metal (MIM) capacitor structure in copper-CMOS circuits using a pad protect layer.

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b. Coolbaugh et al. (US 6,800,921) disclose a method of fabricating a polysilicon capacitor utilizing FET and bipolar base polysilicon layers.

c. Farooq et al. (US 6,791,133) disclose interposer capacitor built on silicon wafer and joined to a ceramic substrate.

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- d. Basceri et al. (US 6,727,140) disclose capacitor with high dielectric constant materials and method of making.
  - e. Cheng et al. (US 6,627,968) disclose integrated capacitor and fuse.
- f. Yang et al. (US 6,423,554) disclose semiconductor device having a capacitor and method for the manufacture thereof.

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nguyen T Ha whose telephone number is 571-272-1974. The examiner can normally be reached on Monday-Friday from 8:30AM to 6:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Dean Reichard can be reached on 571-272-2800 ext. 31. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

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For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Nguyen T. Ha December 15, 2004

ANTHONY DINKINS

THUMARY EXAMINER

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